PATENT 8075-1015

## in the u.s. patent and trademark office0/552709

In re application of

**a**: •

Rikizo HATAKEYAMA et al.

Conf.

Application No. NEW NATIONAL PHASE

Group

Filed October 7, 2005

Examiner

METHOD AND APPARATUS FOR PRODUCING GAS ATOM CONTAINING FULLERENE, AND GAS ATOM CONTAINING FULLERENE

# INFORMATION DISCLOSURE STATEMENT (SUBMISSION CONCURRENT WITH THE FILING OF A NEW PATENT APPLICATION)

Assistant Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

October 7, 2005

Sir:

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Pursuant to 37 C.F.R. §§ 1.97 and 1.98, and in fulfillment of the duty of disclosure under 37 C.F.R. § 1.56, applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

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The patents, publications, or other information submitted for consideration by the Office are listed on PTO-1449, attached hereto.

#### II. COPIES

Copies	of	the U	.s.	patents	or p	ublications	are	not	submitted
 since	the	USPTO	has	waived	thei	r submission	for	app	lications
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- Submitted herewith is a legible copy of (i) each foreign patent; (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed.
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### JC05 Rec'd PCT/PTO 07 OCT 2005

Docket No. 8075-1015

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### INFORMATION DISCLOSURE CITATION IN AN APPLICATION

Attomey Docket No.: 8075-1015

Application No.:

**NEW NATIONAL PHASE** 

Applicant:

Rikizo HATAKEYAMA et al

	(Use several sheets if necessary)		illing Date: October 7, 2005	Group Art Unit:-							
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English language abstract provided for the Examiner's convenience